

**IN THE CLAIMS:**

Claims 2, 4, and 11 through 14 were previously cancelled. Claims 1, 3, 5, 6, 7 and 8 have been amended herein. All of the pending claims are presented below. This listing of claims will replace all prior versions and listings of claims in the application. Please enter these claims as amended.

**Listing of Claims:**

1. (Currently Amended) An overlay target for reducing residue therein from processes for forming semiconductor devices on a wafer comprising:  
a material surface;  
at least three rectangular elongated registration features having adjacent sides of unequal length in said material surface, said at least three rectangular elongated registration features each having a bottom surface, a series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of each of said at least three rectangular elongated registration feature, features, substantially all of said raised lines having surfaces which are substantially coplanar with said material surface, and a series of trenches disposed between said raised lines within each of said at least three rectangular elongated registration feature, features, said at least three rectangular elongated registration features defining a perimeter of a geometric shape, ~~the said~~ at least three rectangular elongated registration features comprising four rectangular elongated registration features defining said overlay target, each of said four rectangular elongated registration features ~~includes~~ including said series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of each of said at least three registration feature, features, and said series of trenches disposed between said raised lines within said four rectangular elongated registration feature, features, said four rectangular elongated registration features defining a continuous perimeter of a rectangle.

2. (Cancelled)

3. (Currently Amended) An overlay target comprising:

a material surface;

at least three rectangular elongated registration features having adjacent sides of unequal length in said material surface, said at least three rectangular elongated registration features each having a bottom surface, a series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of each of said at least three rectangular elongated registration ~~feature,~~ features, substantially all of said raised lines having surfaces which are substantially coplanar with said material surface, and a series of trenches disposed between said raised lines within each of said at least three rectangular elongated registration ~~feature,~~ features, said at least three rectangular elongated registration features defining a perimeter of a geometric shape, said at least three rectangular elongated registration ~~feature~~ features comprising four rectangular elongated registration features defining said overlay target, each of said four rectangular elongated registration features ~~includes~~ including said series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of each of said at least three registration ~~feature,~~ features, and said series of trenches disposed between said raised lines within each of said four rectangular elongated registration ~~feature,~~ features, said four rectangular elongated registration features defining a continuous perimeter of a rectangle.

4. (Cancelled)

5. (Currently Amended) An overlay target comprising:  
a material surface;  
at least one generally square registration feature in said material surface, said at least one generally square registration feature having a bottom surface, and including a series of substantially vertically extending laterally continuous raised lines extending in a parallel manner across said at least one registration feature, and originating at said bottom surface of each of said at least one registration feature, substantially all of said raised lines having surfaces which are substantially coplanar with said material surface, said raised lines being of equal size and dimensions, and a series of trenches disposed between said raised lines within said at least one generally square registration feature, said trenches being of equal width and ~~length~~ length, said at least one generally square registration feature comprising four rectangular elongated registration features defining said overlay target, each of said four rectangular elongated registration features ~~includes~~ including said series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of said at least one registration feature, and said series of trenches disposed between said raised lines within said four rectangular elongated registration ~~feature,~~ features, said four rectangular elongated registration features defining a continuous perimeter of a rectangle.

6. (Currently amended) The overlay target of claim 5, wherein said at least one generally square registration feature includes a plurality of generally square registration features defining said overlay target, each of said plurality of generally square registration features ~~includes~~ including said series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of said at least one registration feature, and said series of trenches disposed between said raised lines within said at least one generally square registration feature.

7. (Currently amended) The overlay target of claim 6, further comprising at least one rectangular elongated registration feature including said series of substantially vertically extending laterally continuous raised lines originating at a bottom surface of said four rectangular elongated registration ~~feature~~ features.

8. (Currently Amended) A semiconductor wafer comprising:  
a semiconductor substrate having a material surface; and  
an overlay target in said material surface, having at least three rectangular elongated registration features having adjacent sides of unequal length, said at least three rectangular elongated registration features each having a bottom surface comprising at least one series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of each of said at least three rectangular elongated registration ~~feature~~ features, substantially all of said raised lines having surfaces which are coplanar with said material surface, and a series of trenches disposed between said raised lines within each of said at least three rectangular elongated registration ~~feature~~ features, said at least three rectangular elongated registration features defining a perimeter of a geometric shape, ~~the~~ said at least three rectangular elongated registration features comprising four rectangular elongated registration features defining said overlay target, each of said four rectangular elongated registration features ~~includes~~ including said at least one series of substantially vertically extending laterally continuous raised lines originating at said bottom surface of each of said at least three registration ~~feature~~ features, and said series of trenches disposed between said raised lines within said four rectangular elongated registration ~~feature~~ features, said four rectangular elongated registration features defining a continuous perimeter of a rectangle.

9. (Previously Presented) The semiconductor wafer of claim 8, wherein said at least one series of substantially vertically extending laterally continuous raised lines is etched into said semiconductor substrate.

10. (Previously Presented) The semiconductor wafer of claim 8, wherein said at least one series of substantially vertically extending laterally continuous raised lines is etched into a material layer overlying said semiconductor substrate.

11.-14. (Cancelled)

15. (Currently amended) The semiconductor wafer of claim 8, wherein said at least one series of substantially vertically extending laterally continuous raised lines comprises a first series of raised lines disposed in a rectangular elongated registration ~~feature~~, feature, said overlay target further comprising ~~and a~~ a second series of raised lines disposed in a generally square registration feature.

**IN THE DRAWINGS:**

The attached sheets of drawings include changes to FIGS. 4, 11, 12 and 13. These sheets, which include FIGS. 3 and 4, 11 and 15 and 12, 13 and 14, replace the original sheets including FIGS. 3, 4, 11, 12, 13, 14 and 15.

Specifically, FIG. 4 has been revised to add the reference numeral --10-- with appropriate lead line; FIG. 11 has been revised to add the reference numeral --39-- with appropriate lead line; and FIGS. 12 and 13 have been revised to add the designation --(*PRIOR ART*)-- below the figure number. No new matter has been added.